



FIG.2

EXPOSURE  
LIGHT  
WAVELENGTH

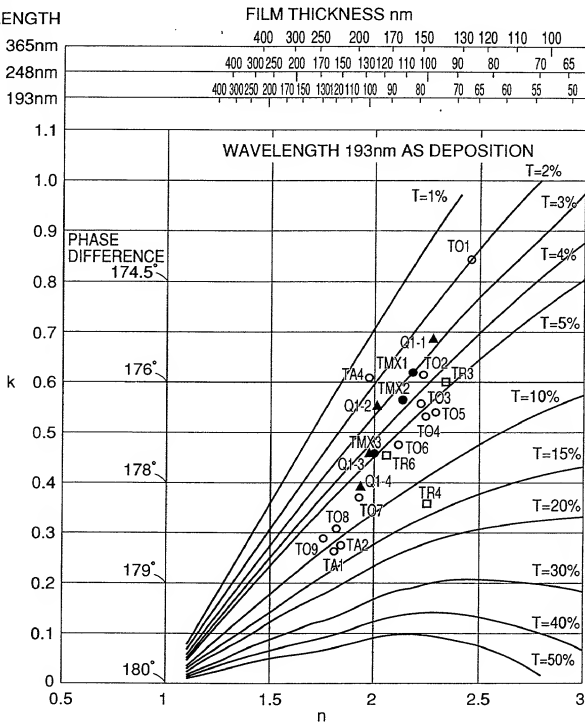


FIG.3

EXPOSURE  
LIGHT  
WAVELENGTH

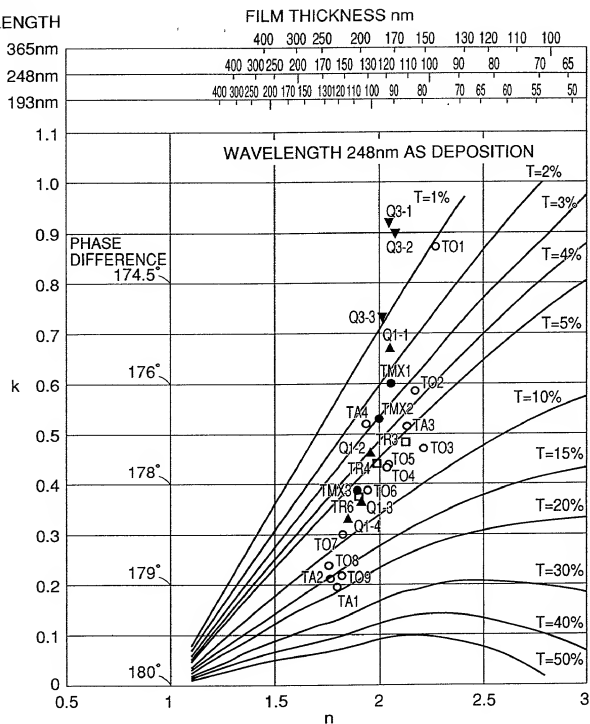


FIG.4

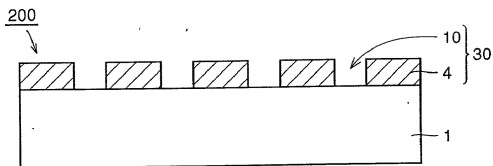


FIG.5A



FIG.5B

ELECTRIC FIELD  
ON THE MASK

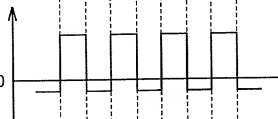


FIG.5C

LIGHT INTENSITY  
ON THE WAFER

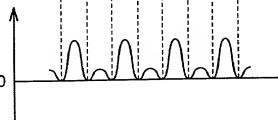


FIG.6

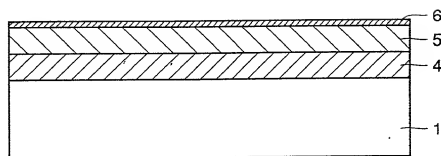


FIG.7

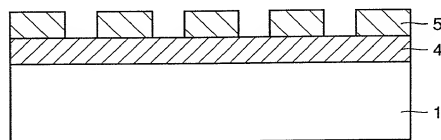


FIG.8

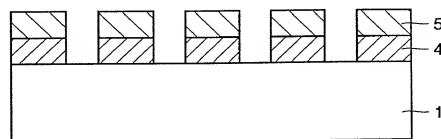


FIG.9

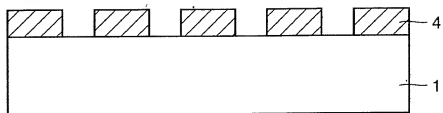


FIG.10

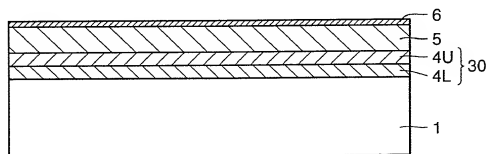


FIG.11

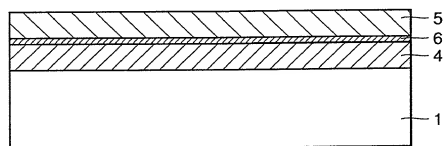


FIG.12

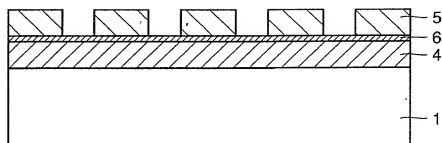


FIG.13

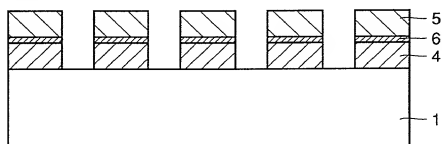


FIG.14

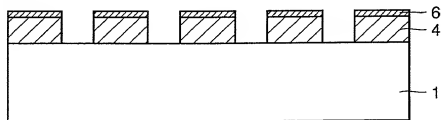


FIG. 15

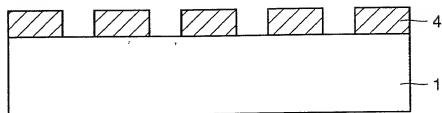


FIG. 16A

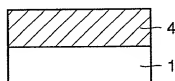


FIG. 16B

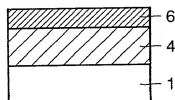


FIG. 17A

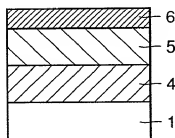


FIG. 17B

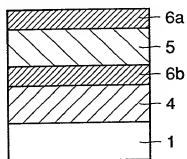




FIG.18

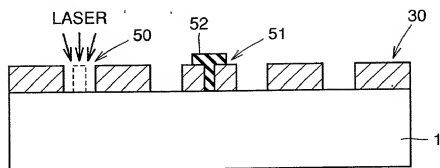


FIG.19

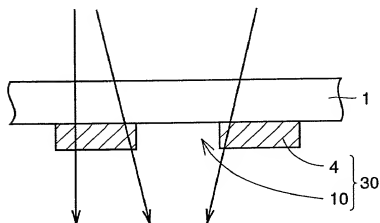


FIG.20

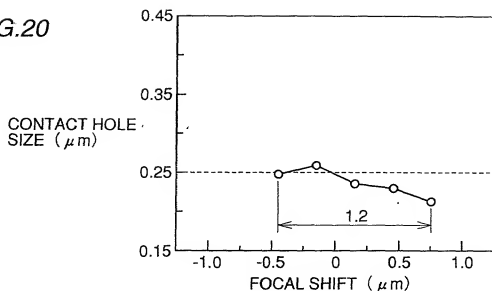


FIG.21

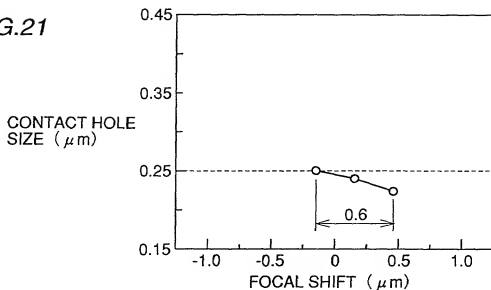


FIG.22

